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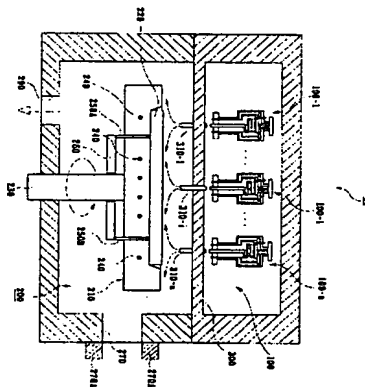
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(54) MULTI-FUNCTION CHAMBER**(57) Abstract:**

PURPOSE: A multi-function chamber is provided to diversify processes using the same chamber like a diffusion process, a chemical deposition process and a dry cleaning process by dividing reaction gas activation and surface reaction.

CONSTITUTION: Reaction gas is induced to a reaction gas induction unit. A reaction gas activation heating unit activates the induced reaction gas. A reaction gas pipe makes the reaction gas absorb thermal energy without heat radiation. A total internal reflection coating is performed regarding an internal thermal reflecting part and an external thermal radiation intercepting part to prevent thermal radiation. A reaction gas spraying part uniformly sprays the activated reaction gas.



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